



제25회 한국반도체학술대회

The 25th Korean Conference on Semiconductors

2018년 2월 5일(월)-7일(수), 강원도 하이원리조트 컨벤션 호텔

2018년 2월 7일(수), 16:15-17:30

Room C (함백, 5층)

D. Thin Film Process Technology 분과

[WC4-D] Thin Films for Memories and Transistors II

좌장: 김건환(한국화학연구원), 최병준 교수(서울과학기술대학교)

<p>WC4-D-1 16:15-16:30</p>	<p>Si Doping in HfO₂ by Atomic Layer Deposition for Ferroelectric Tunneling Junction Applications Yong-Woon Lee¹, Jong-Seo Park^{2,3}, and Han-Bo-Ram Lee^{1,2} <i>¹Department of Materials Science and Engineering, Incheon National University, ²Innovation Center for Chemical Engineering, Incheon National University, ³School of Electrical and Electronic Engineering, Yonsei University</i></p>
<p>WC4-D-2 16:30-16:45</p>	<p>The Influence of High Pressure Annealing on Hf_{0.5}Zr_{0.5}O₂ Ferroelectric Films Taeho Kim and Sanghun Jeon <i>Department of Applied Physics, Korea University</i></p>
<p>WC4-D-3 16:45-17:00</p>	<p>Directly Drawn Carbon Nanotube Transistors with a High Device Yield and Uniform Performance Jinhee Park, Bongsik Choi, Jinsu Yoon, Yongwoo Lee, Jungmin Han, Jieun Lee, Yeamin Kim, Dong Myong Kim, Dae Hwan Kim, and Sung-Jin Choi <i>School of Electrical Engineering, Kookmin University</i></p>
<p>WC4-D-4 17:00-17:15</p>	<p>Characteristics of Activation and Post-Metal Annealing Using Microwave in Phosphorus-implanted SOI MOSFETs Gi-yong Lee and Won-Ju Cho <i>Department of Electronic Material Engineering, Kwangwoon University</i></p>
<p>WC4-D-5 17:15-17:30</p>	<p>반도체/OLED용 화학증착소재의 열·화학적 안정성 평가 심섭^{1,2}, 안종기¹, 강고루¹, 강연태¹, 김하영^{1,2}, 손주희³, 김진태^{1,2}, 정낙관¹, 허규용³, 윤주영^{1,2} <i>¹한국표준과학연구원 소재에너지융합측정센터, ²과학기술연합대학원대학교 나노재료공학, ³한국화학연구원 신뢰성평가센터</i></p>